

# Mono Silicon Wafer

Data Sheet

**P-Type** 210±0.25mm

PT.Standard Energy Indonesia

Email [info@standard-thailand.com](mailto:info@standard-thailand.com)

Web [www.ptstandard-energy.com](http://www.ptstandard-energy.com)

### Material Performance Parameters

Conductivity Type	P	P/N type tester
Doped element	Gallium	/
Crystallinity	Single crystal	Priority etching technology (FSTM F47-88)
Dislocation density/pcs/cm <sup>2</sup>	≤500	Priority etching technology (FSTM F47-88)
Surface orientation	<100>±3°	X-ray diffractometer
Lateral crystal orientation	<010>, <001>±3°	X-ray diffractometer
Oxygen content (ppma)	≤16	FTIR (ASTM F121-83)
Carbon content (ppma)	≤1	FTIR (ASTM F123-91)
Lifetime (μs)	≥70	BCT-400
Resistivity (Ω.cm)	0.4-1.1	Silicon wafer automatic inspection equipment

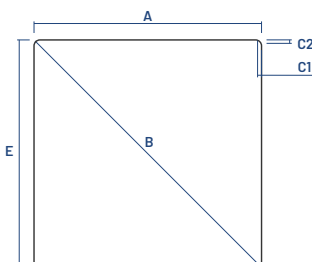
### Geometric Rule Parameters

Chamfered edge shape	Right angle	/
Wafer margins (mm)	210±0.25mm	Silicon wafer automatic inspection equipment
Wafer diameter (mm)	φ295±0.25mm	Silicon wafer automatic inspection equipment
Arc length projection (mm)	1.41±0.5mm	Silicon wafer automatic inspection equipment
Perpendicularity	90.15°	Silicon wafer automatic inspection equipment
Thickness specification (μm)	150±10	Silicon wafer automatic inspection equipment
	155±10	Silicon wafer automatic inspection equipment

### Appearance Quality

Surface quality	No visible pollution	Silicon wafer automatic inspection equipment
	No color difference, No bright lines	
Edge Chipping	Depth≤0.3mm , Length ≤0.5mm,	Silicon wafer automatic inspection equipment
	Counts≤2/pcs, no V-shaped	
Saw mark (μm)	≤15	Silicon wafer automatic inspection equipment
Warp/bending degree (μm)	≤40	Silicon wafer automatic inspection equipment
TTV (μm)	≤25	Silicon wafer automatic inspection equipment
Micro-crack/void	None	Silicon wafer automatic inspection equipment

Wafer dimensions



Size: 210±0.25mm

A: 210±0.25mm

E: 210±0.25mm

B: φ 295±0.25mm

C1: 1.41±0.5mm

C2: 1.41±0.5mm